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(12) **United States Design Patent**
Li

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(54) **PROCESSING CHAMBER FOR MANUFACTURING SEMICONDUCTORS**

(75) Inventor: **Yicheng Li**, Narashino (JP)

(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(**) Term: **14 Years**

(21) Appl. No.: **29/278,802**

(22) Filed: **Apr. 10, 2007**

(30) **Foreign Application Priority Data**

Oct. 10, 2006 (JP) 2006-027245

(51) **LOC (9) Cl.** **13-03**
(52) **U.S. Cl.** **D13/182**
(58) **Field of Classification Search** D13/182; D6/509, 577; D9/456; D14/214, 215, 219, D14/471, 475, 483; D12/525, 538, 547, D12/562, 570; D17/24; 118/715, 724, 725, 118/728, 729; 156/345.24, 345.51; 216/67; 219/390; 324/765
See application file for complete search history.

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Primary Examiner—Selina Sikder
(74) *Attorney, Agent, or Firm*—Oblon, Spivak, McClelland, Maier & Neustadt, P.C.

(57) **CLAIM**

The ornamental design for a processing chamber for manufacturing semiconductors or the like, as shown and described.

DESCRIPTION

FIG. **1** is a top and right front perspective view of a processing chamber for manufacturing semiconductors or the like, showing my new design;

FIG. **2** is a front elevational view thereof;

FIG. **3** is a rear elevational view thereof;

FIG. **4** is a right side elevational view thereof, the left side elevational view being a mirror image of the side view shown;

FIG. **5** is a top plan view thereof;

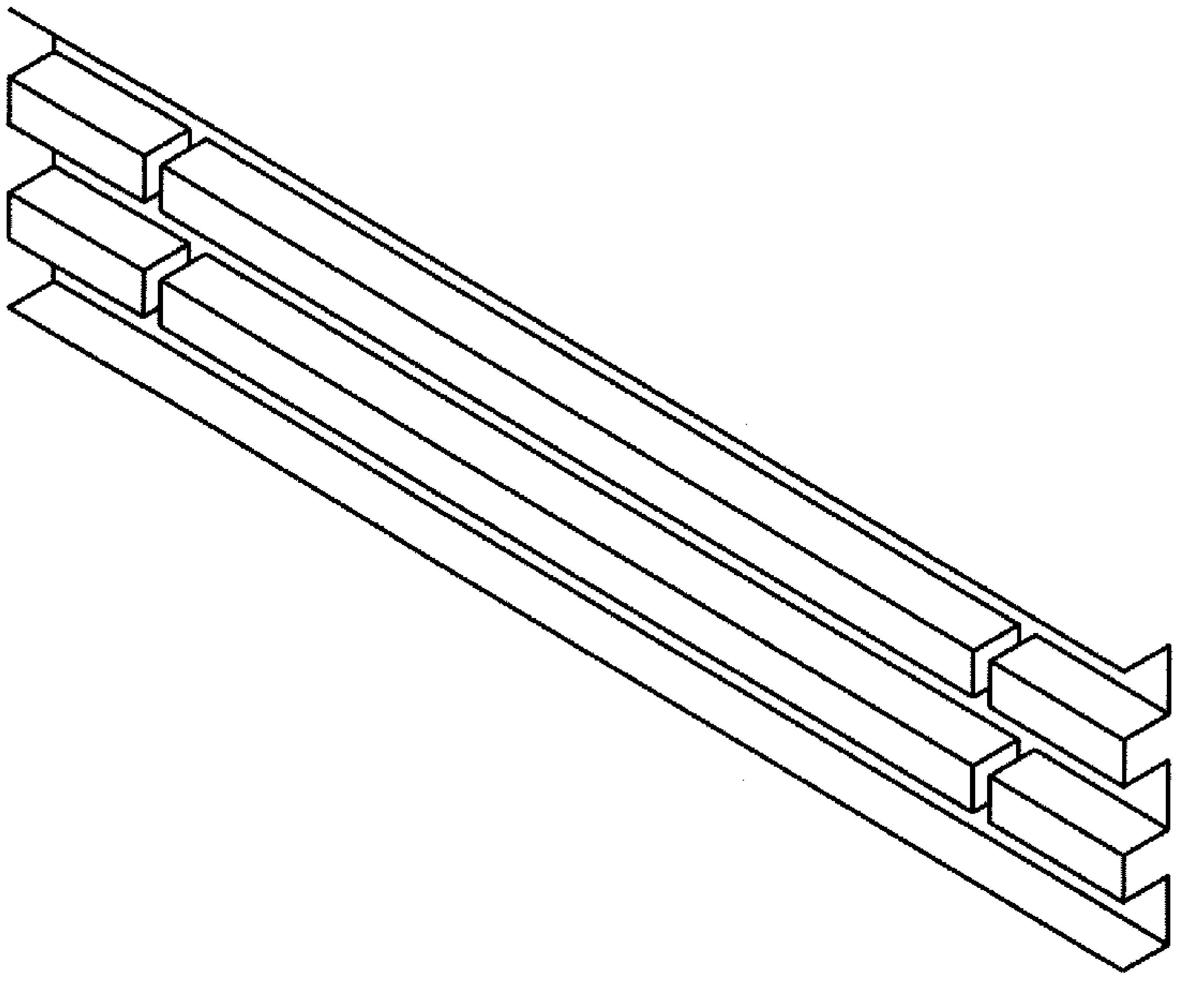
FIG. **6** is a bottom plan view thereof;

FIG. **7** is a cross-sectional view thereof taken in the direction of the arrows on line **7**—**7** of FIG. **2**; and,

FIG. **8** is a top and right front perspective view thereof in the state of use.

The broken line showing in the figures is for illustrative purposes only and forms no part of the claimed design.

1 Claim, 8 Drawing Sheets



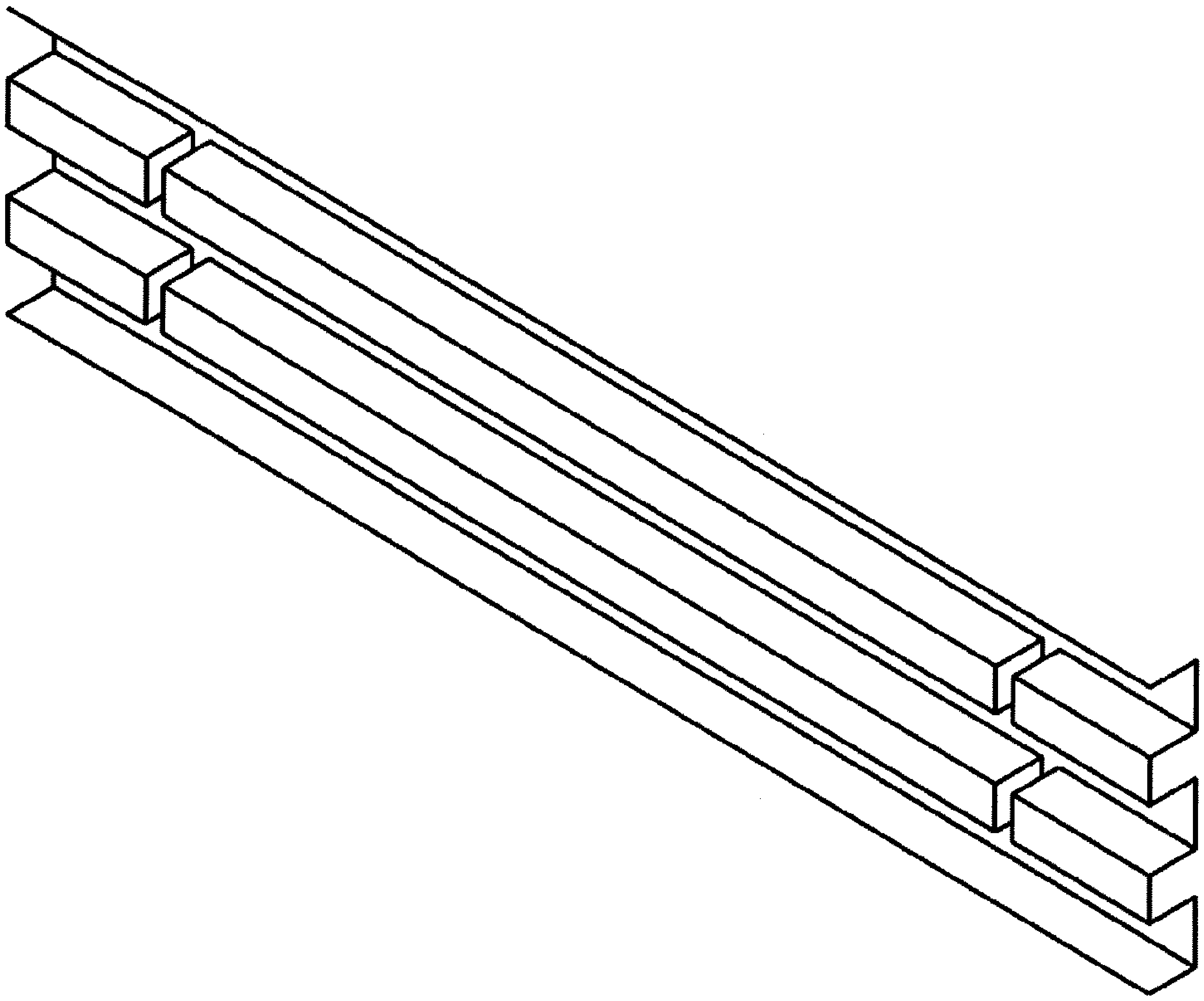


FIG. 1

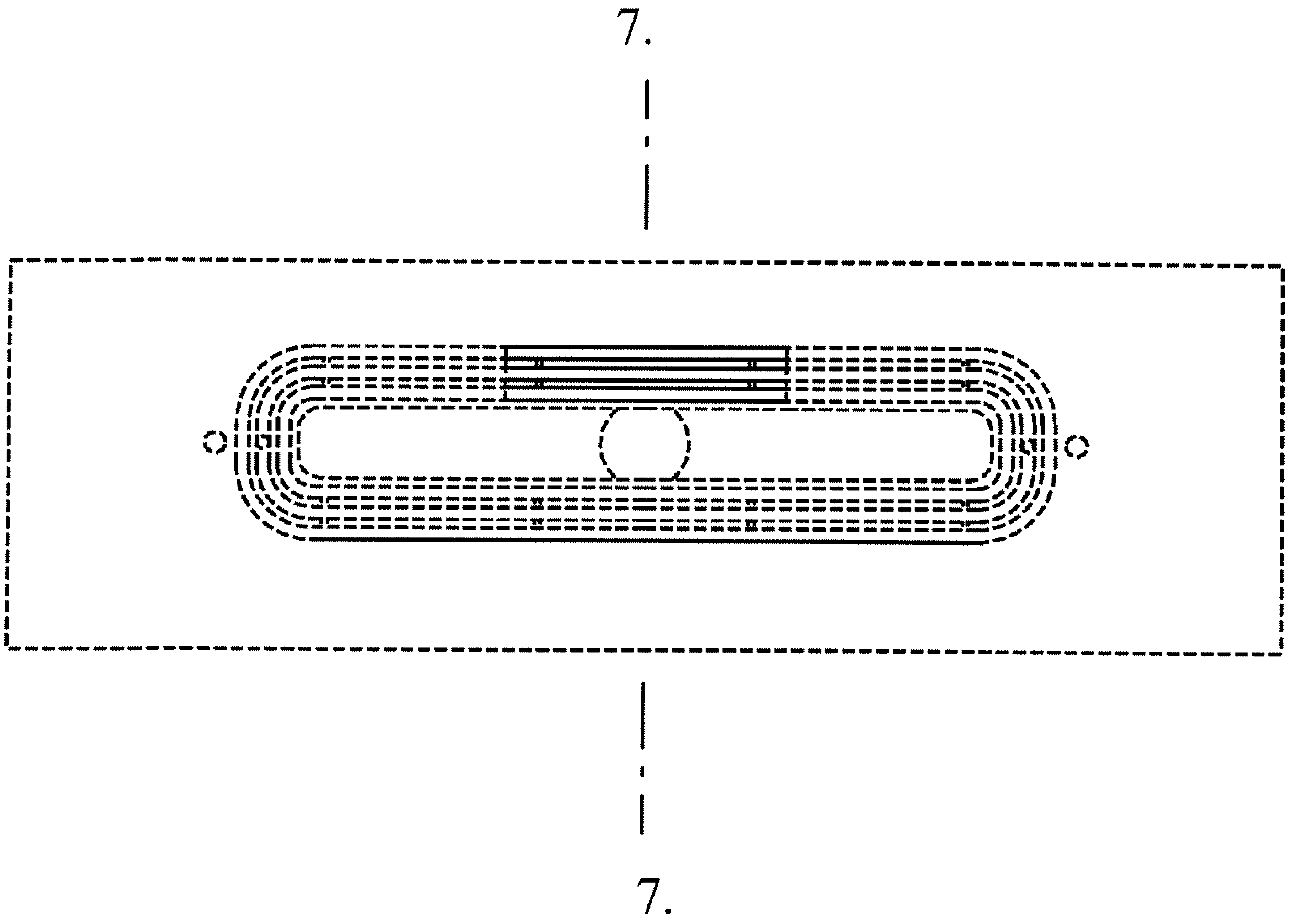


FIG. 2

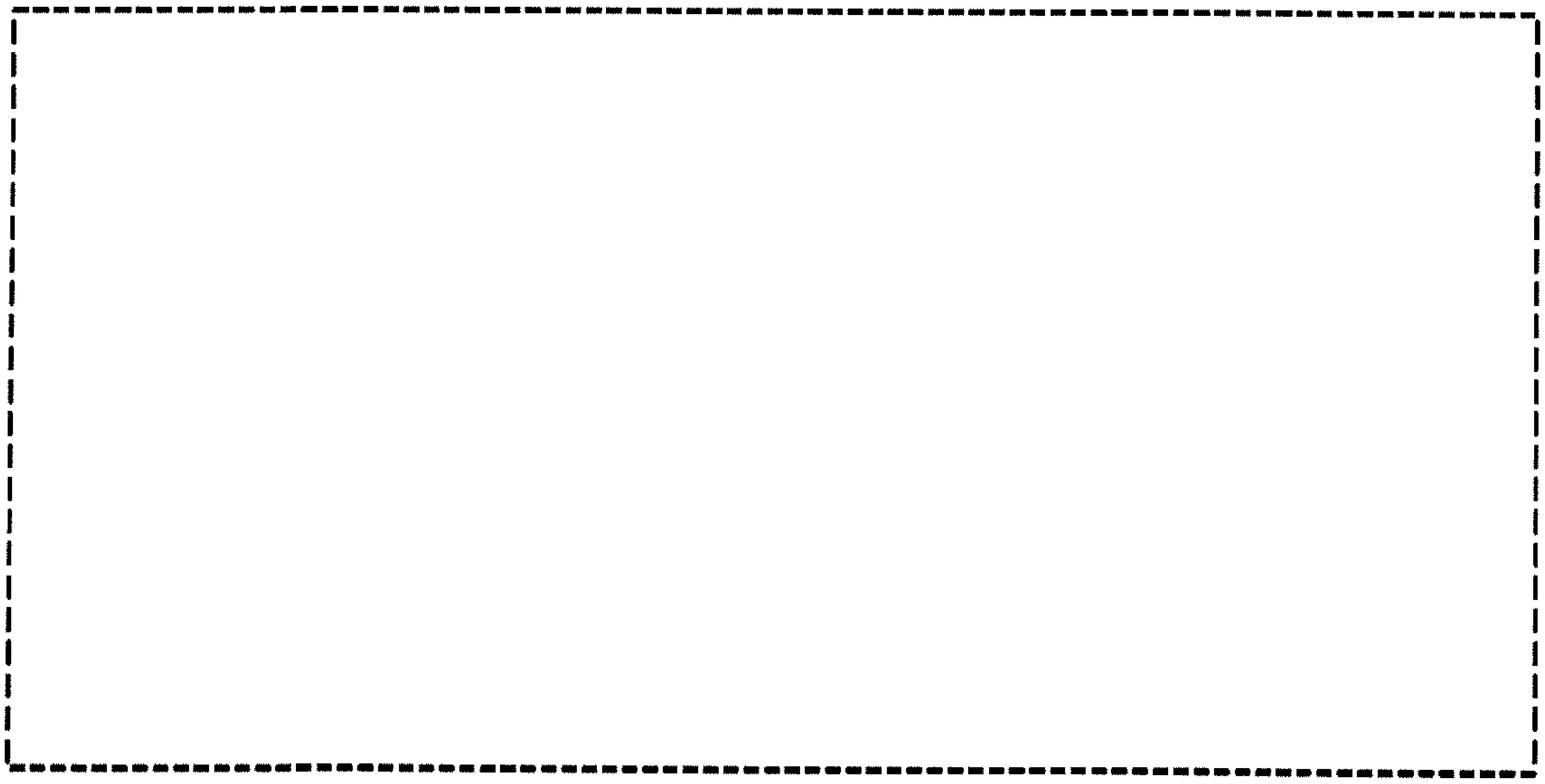


FIG. 3

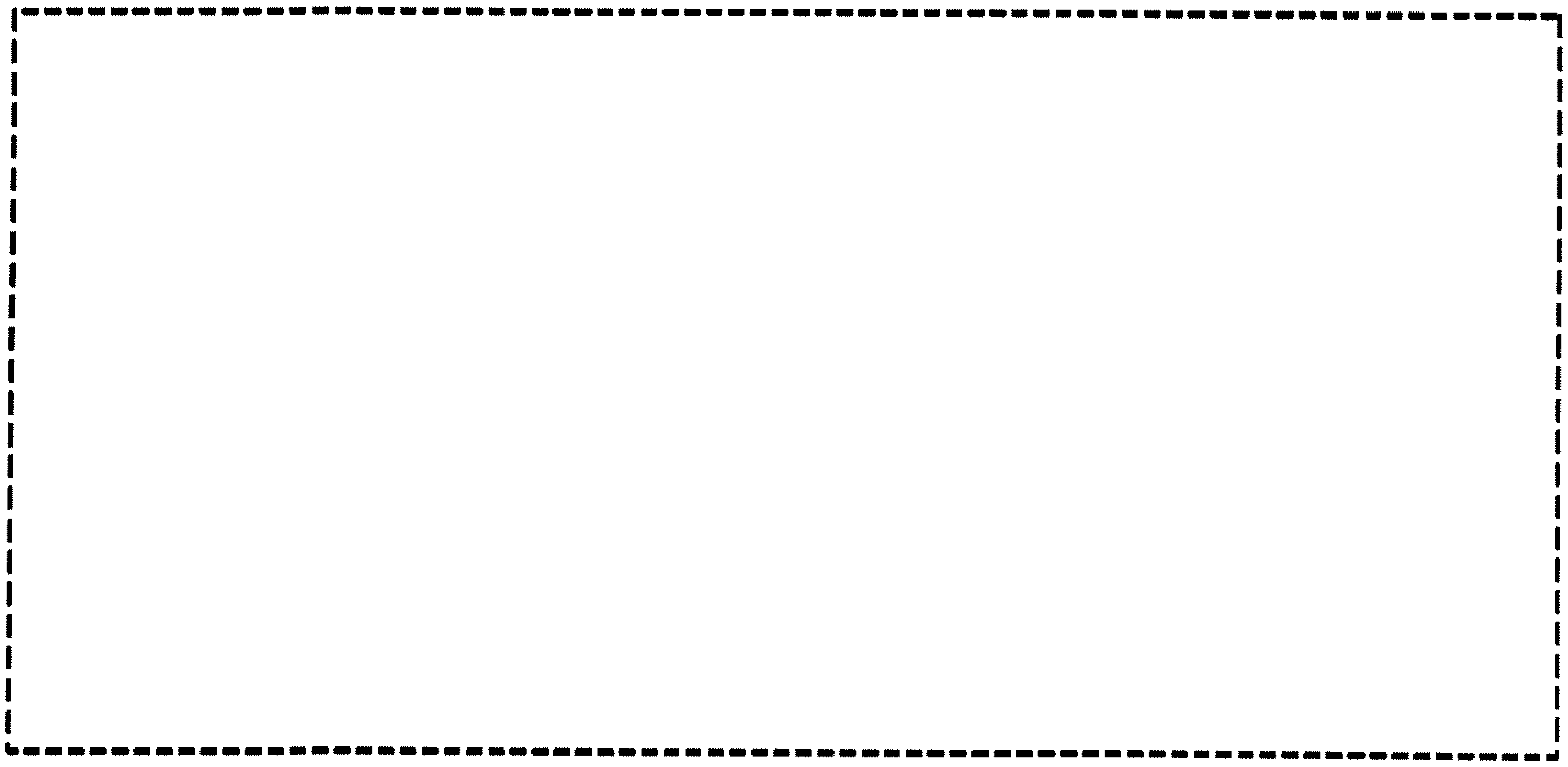


FIG. 4

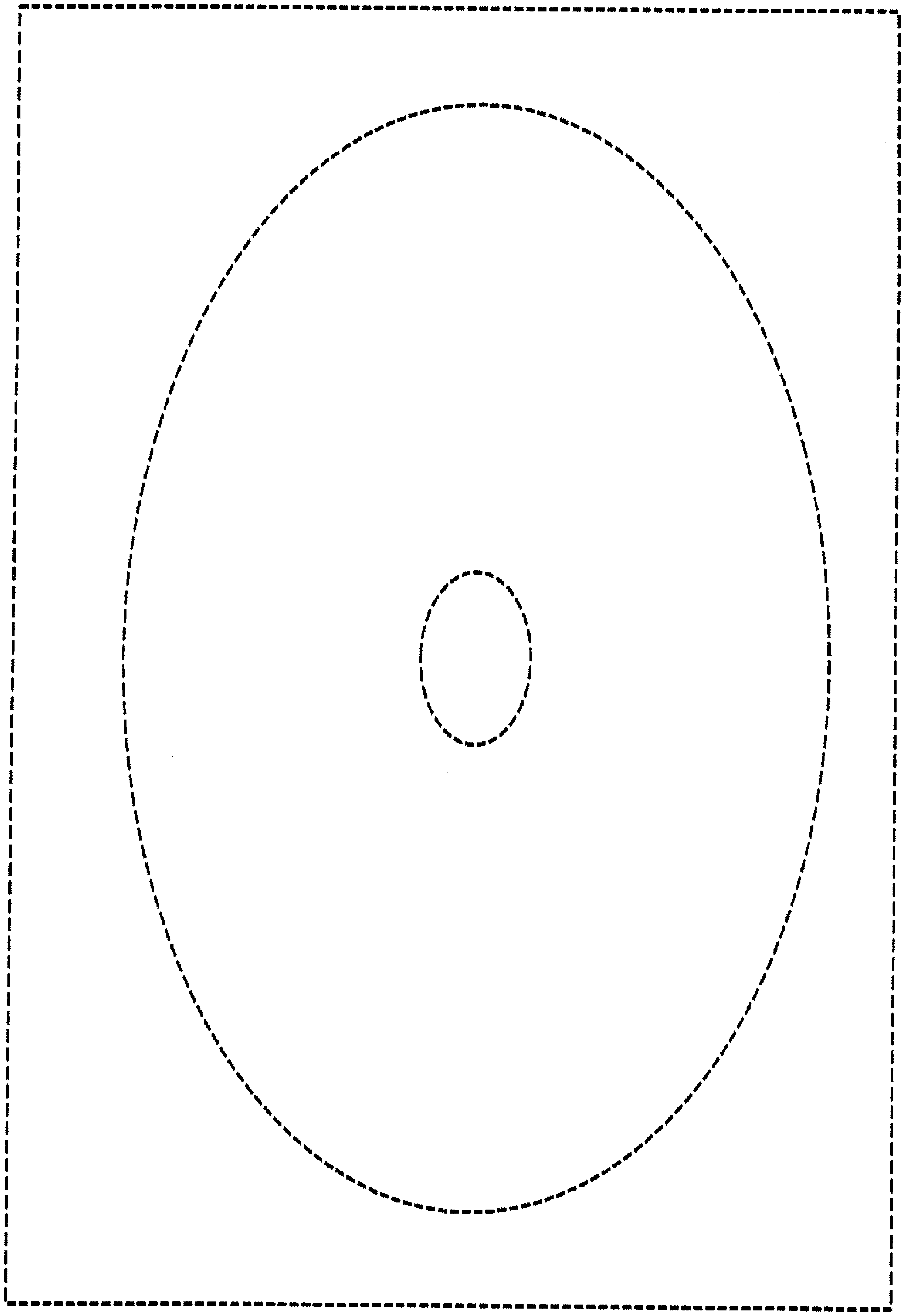


FIG. 5

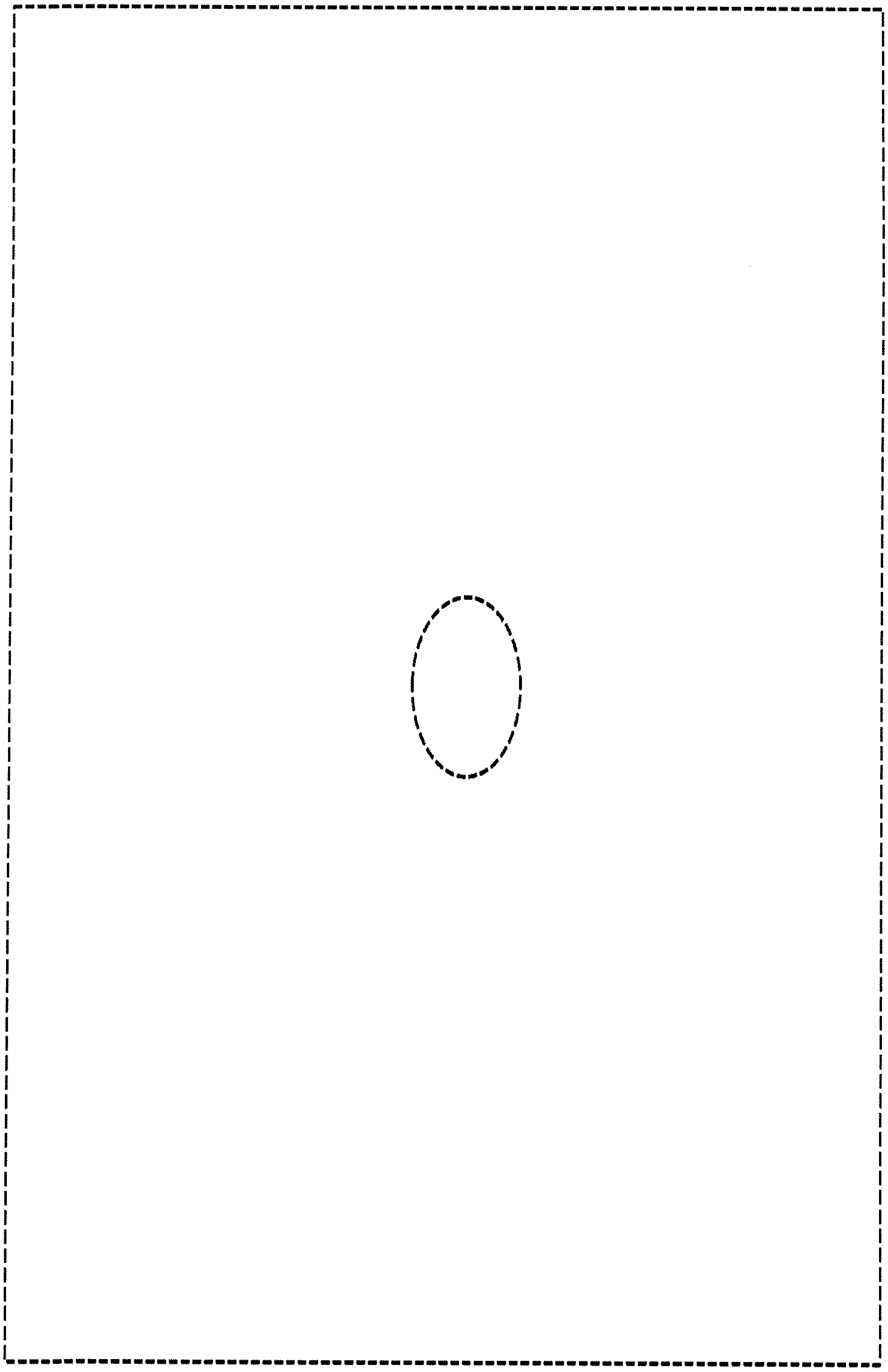


FIG. 6

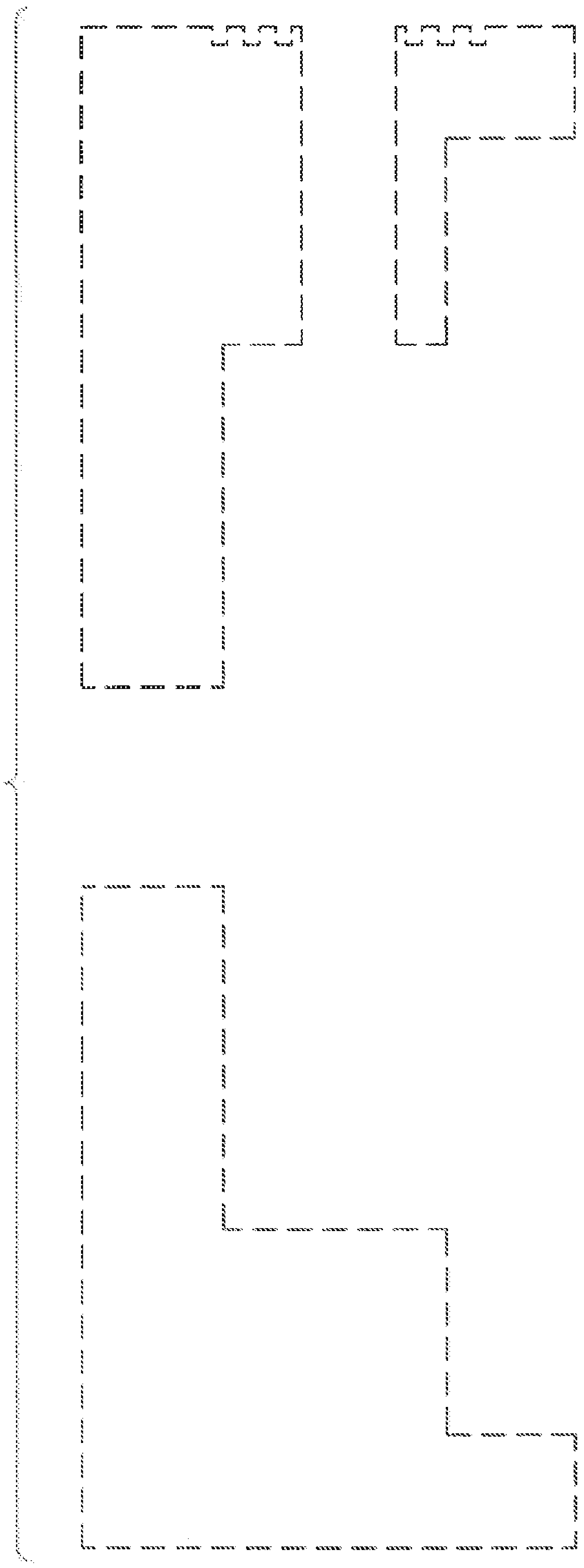


Fig. 7

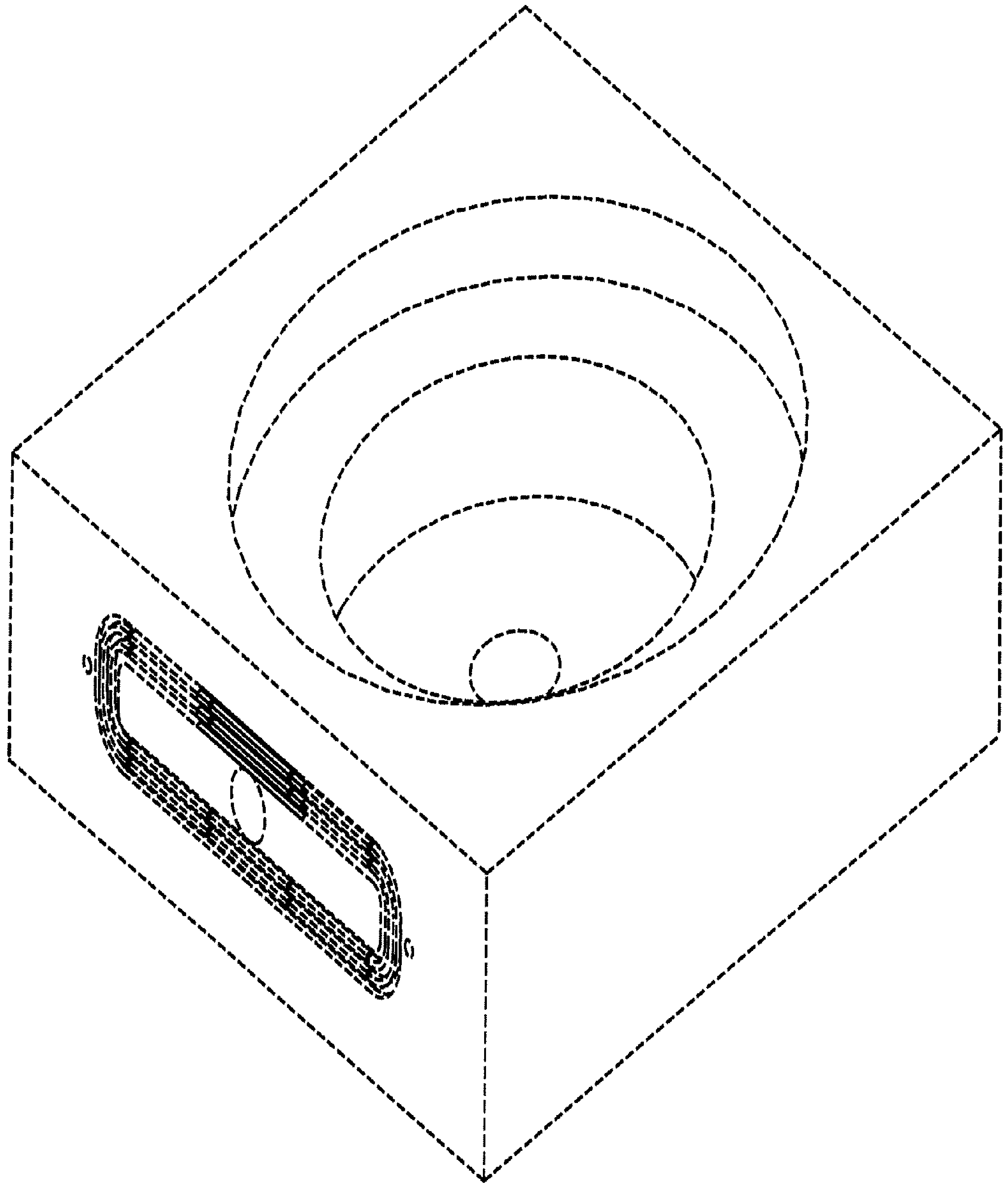


FIG. 8